

EP-DT Detector Technologies

# Silicon Detector R&D in DT

## **EP-DT Group Meeting**

09/12/2021

Florian Dachs (EP-DT-DD) Katharina Dort (EP-DT-TP) Anja Himmerlich (EP-DT-SSD)

### Katharina Dort [DT-TP]

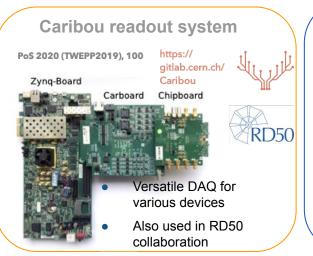
# https://

gitlab.cern.ch/

corryvreckan/

# Pixel detector R&D in DT-TP

- Pixel detector R&D for future collider detectors, emphasis on Higgs factories
  - High precision, low mass
- Pursued within EP R&D programme and various collaborative frameworks (AIDAinnova, CLICdp) and strong connection to EP-ESE + DESY + UniGE
- Simulation-based sensor optimisation and experimental verification with technology demonstrators
- Team members: Justus Braach, Eric Buschmann, Dominik Dannheim, Katharina Dort, Peter Švihra







Built + maintain high-rate telescope at SPS

Software tools for the (HEP) community

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CERN

- Corryvreckan test-beam reconstruction and analysis
- Allpix Squared Monte Carlo simulation framework for end-to-end simulation of silicon sensors



https:// gitlab.cern.ch/ allpix-squared/ allpix-squared



EP R&D

**Detector Technologies** 

AIDA



2021 JINST 16 P03008

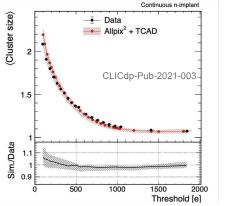


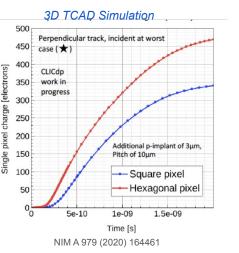


# Pixel detector R&D in DT-TP

**Sensor Optimisation** 

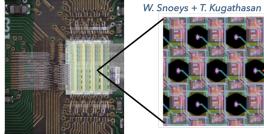
- Combined electrostatic
  3D TCAD + transient MC simulation for
  - Precise sensor modelling
  - High simulation rates
    NIM A 964 (2020) 163784
- Design optimisation for fast sensor timing
- Hexagonal pixel layout for improved performance





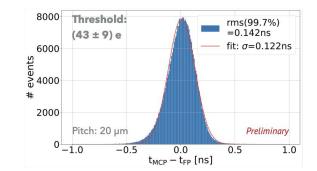
Monolithic CMOS sensor with sub-nanosecond timing

Modified 180 nm CMOS imaging process



*Pixel pitch: 8.66 μm - 20 μm* 

• Time resolution < 150 ps



Katharina Dort [DT-TP]

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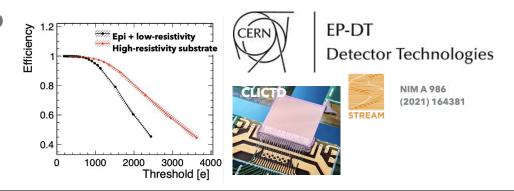
Hexagonal pixel layout

CERN

# Pixel detector R&D in DT-TP

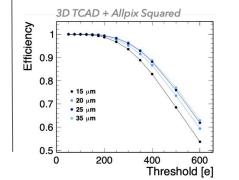
Advances materials for monolithic sensors

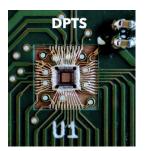
- Larger active sensor volume
- Improved detector performance: efficiency, spatial + time resolution https://agenda.linearcollider.org/event/9211/contributions/49443/



## Monolithic sensors in 65nm CMOS

- Process optimisation using simulations
- Characterisation of digital test-chip (DPTS) with Caribou DAQ
- Detailed test-beam studies spring next year
  - Timing performance + comparison to simulation



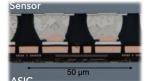


### Novel fine-pitch hybridisation

- Development + characterisation of small-pitch (25 μm) bump-bonding process
   CERN-THESIS-2020-338
- Proof-of-principle for alternative in-house bonding technique using Anisotropic Conductive Film (ACF)
- Also used for module integration (see part from Florian) Conductive ACF ball



### CLICpix2 hybrid assembly (IZM)



https://agenda.linearcoll ider.org/event/9211/con

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Flip-chip bonder at UniGE

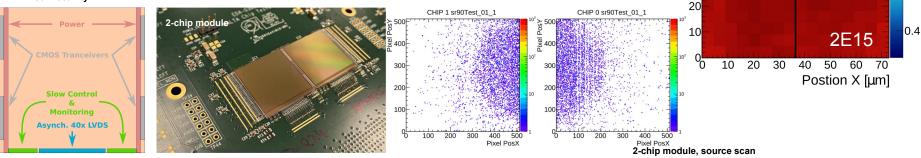
## CMOS pixel detector R&D and module development (CERN)

Florian Dachs\*, Abhishek Sharma, Julian Weick, Peter Svihra, Mateus Vicente, Milou van Rijnbach, Dominik Dannheim, Petra Riedler

EP-DT & WP 1.3 & EP-ADE in close collaboration with the QARTIab and Bondlab at the DSF, working closely CERN services and with institutes (e.g. Univ. of Geneva)

- Studies performed on the monolithic CMOS pixel chip "MALTA" designed for high radiation hardness and produced in the 180 nm TowerJazz process
  - 2x2 cm<sup>2</sup> overall size, 36.4 µm symmetric pixel pitch
  - fast detection and readout compatible with 40MHz event rate
  - redundant CMOS transceivers for chip-to-chip data and allows direct chip-to-chip powering
- Focus on the study of various interconnection techniques and chip-to-chip transmission of power and data to build large scale, low-mass modules
- **Optimize base wafer material**, chips produced on different epi wafers as well as on high res CZ wafers
- Performance tests and qualification on chip and module level

### MALTA connectivity



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Efficiency: 95.1±0.2 % @ 240 e MALTA, Cz silicon, NGAP, 2E15 1MeV n\_/cm<sup>2</sup>, SUB @ -55V, sector 2

ATLAS

Digita

[mm]

60

50

40

30

Position Y

Collection

electrode

MALTA pixel cell

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EP

R&D

Efficiency [%/100]

0.8

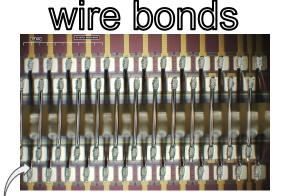
0.6

## CMOS pixel detector R&D and module development



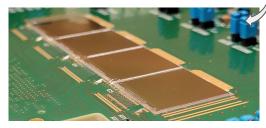
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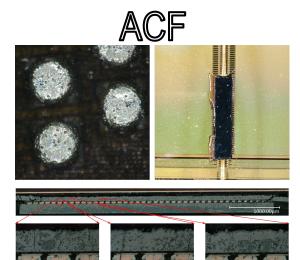
Study interconnection techniques and establish assembly procedures



Al wedge wire bonding as baseline to study chip performance

**Functioning 2-chip** and 4-chip modules assembled and currently undergoing testing

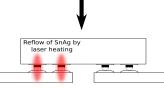




- ACF connections studies on chip interconnection with a Silicon bridge
- multiple glues tested
- multiple mech. supports developed

# laser reflow

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Laser reflow technique where Sn tipped Cu studs are bonded to Ni/Au plated pads

ENIG plating done by DT **Micro-Pattern Technologies** lab (Rui de Oliveira)

Technique shows high quality bonds on broken assemblies

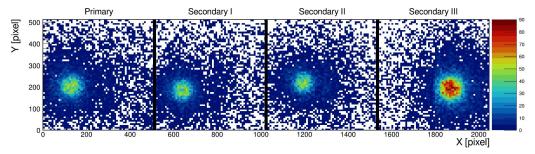


## CMOS pixel detector R&D and module development (

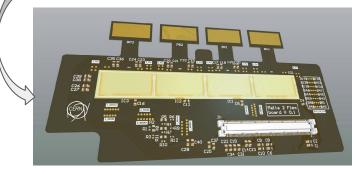
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Study chip-to-chip power and data transfer - performance tests on 2-chip and 4-chip modules

Source scan on continuously read out **4-chip module** (total size 8x2 cm<sup>2</sup>) **Readout full module via one chip only:** 

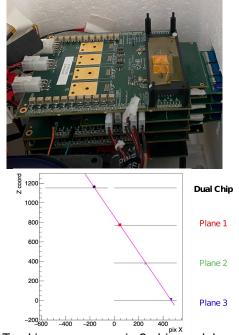


Studies on current 4-chip board enable development towards light-weight flex-based 4-chip module



- Chip-2-flex mounting
- Designed for direct pad-to-pad bonding with various interconnection techniques!
- Design completed

### 2-chip board in cosmic telescope:



- Tracking across gap in 2-chip modules and efficiency studies ongoing!
- Planning for test-beam measurements in 2022

## **Radiation Hard Silicon Detectors**



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## Work performed by the EP-DT Solid State Detectors (SSD) team

Frameworks:





SSD: 1.5 Staff, 2 Fellows, 3 PhD students & visiting scientists + collaborators SSD labs in bldgs. 28 and 186

## RD50 – Radiation hard semiconductor devices for very high luminosity colliders

- $\Rightarrow$  66 Institutes with 420 members, collaboration formed in 2001
- ⇒ CERN SSD acting as host lab, providing co-spokesperson, the budget holder and admin support (Veronique Wedlake)
- ⇒ CERN SSD scientific contributions in 4 main areas

Timing detectors for harsh radiation environments

in particular: LGAD – Low Gain Avalanche Diodes

Defect formation in defect engineered semiconductors

in particular: acceptor removal

Modelling of radiation damage on microscopic and device level

in particular: NIEL – Non Ionizing Energy Loss

Characterization tools for irradiated silicon devices

in particular: TPA-TCT - Two Photon Absorption - Transient Current Technique

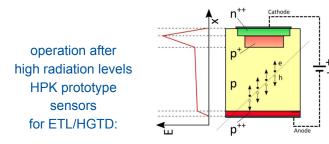
## **Radiation Hard Silicon Detectors**

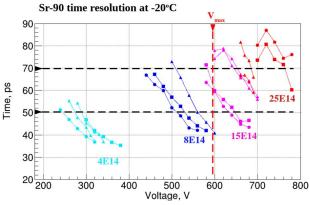


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### Example on Sensor Development:

### LGAD – Low Gain Avalanche Diodes

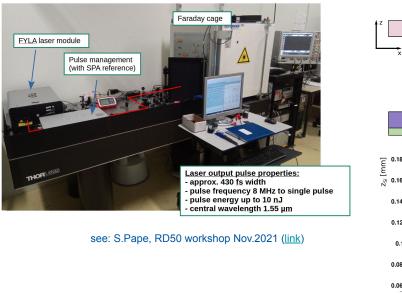


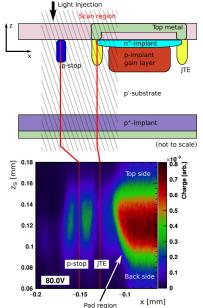


### Example on Characterization tools:

TPA-TCT: Two Photon Absorption – Transient Current Technique

⇒ Laser induced charge generation in silicon devices used to
 evaluate detector properties (3D resolution: 1.5 um x 1.5 um x 15 um)
 ⇒ Hardware financed by a CERN Technology Transfer grant





see: E.Curras, EP-RD seminar 06.12.21 (link)

## Radiation Hard Silicon Detectors

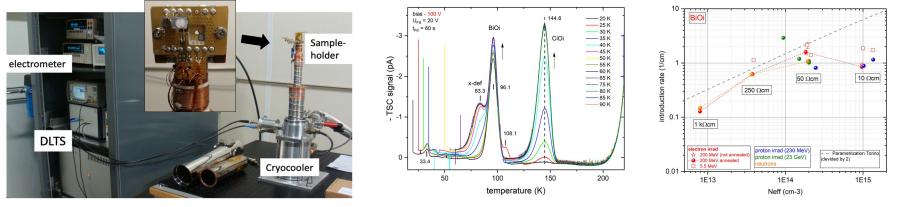


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BO

#### Radiation induced degradation of the LGAD gain: **Acceptor Removal Effect** $\Rightarrow$ Deactivation of Boron as shallow dopant neutron irradiated W7 samples (<sup>90</sup>Sr setup) et al. 2015 JINST 10 P07006 80000 • W7-C9 70000 e Most typical radiation induced reaction: ▲ W7-I6 • W7-110 60000 charge 50000 Conduction Band Conduction Band E $Si_i + B_s \rightarrow B_i$ 40000 30000 p++ **Radiation Damage** 20000 B acceptor 2.1015 cm-2 1000 $B_i + O_i \rightarrow B_i O_i$ Moll, PoS(Vertex 2019) 027 Ev Ev Valence Band alence Band 1000 1500 bias voltage [V]

Defect spectroscopy: Deep-level-transient spectroscopy (DLTS) & Thermally stimulated current technique (TSC)



RD50 workshop 202

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A. Himmerlich